

SEMICONDUCTOR STRUCTURE AND METHOD FOR MANUFACTURING SAME

ABSTRACT

Embodiments of the disclosure relate to the field of semiconductors, and provide a semiconductor structure and a method for manufacturing the same. The semiconductor structure includes: a base, including bit lines and semiconductor channels that are respectively arranged at intervals, in which a bit line extends in a first direction, a semiconductor channel is located on partial top surface of the bit line, and in a direction perpendicular to a top surface of the bit line, the semiconductor channel includes a first region, a second region and a third region arranged in sequence; a dielectric layer, located between two adjacent ones of the bit lines and on a surface of the semiconductor channel; a first gate layer, surrounding the dielectric layer of the second region and extending in a second direction, in which the first direction is different from the second direction; a second gate layer, surrounding the dielectric layer of the third region, in which, in the direction perpendicular to the top surface of the bit line, the second gate layer is spaced apart from the first gate layer; and an insulation layer, located between the adjacent semiconductor channels on the same bit line and isolating the first gate layers and the second gate layers on the adjacent dielectric layers. According to the embodiments of the disclosure, the electrical properties of the semiconductor structure are improved.

<Fig. 2>